



DOCKET NO. 1076.1063

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:

Yuuichi TACHINO et al.

Group Art Unit: 1763

Serial No: 09/775,653

Examiner: Anna M. Crowell

Filed: February 5, 2001

Confirmation No.: 9294

For: PLASMA ETCHING METHOD AND APPARATUS

#8A
1/3/03
mw

AMENDMENT

RECEIVED

JAN 30 2003

TC 1700

Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

This is responsive to the non-final Office Action mailed September 25, 2002, having a shortened period for response set to expire on December 25, 2002. A petition and fee for a ONE-month Extension of Time is enclosed, thereby extending the response period to January 25, 2003.

The following amendments and remarks are respectfully submitted.

IN THE CLAIMS:

Please AMEND claims 2, 3, 7, 10, 11, 13, 17 and 18, as follows. Also, please ADD new claims 21-23.

2. (ONCE AMENDED) A plasma etching apparatus comprising:
a reaction tube made of a dielectric material in the form of a cylinder;
a high frequency coil antenna located around the reaction tube for generating a plasma inside the reaction tube, the high frequency coil antenna having a portion that produces a relatively large capacitive coupling with the reaction tube, a power supply terminal connected to a plasma source high frequency power supply, and a ground terminal connected to a ground;

and

01/28/2003 CCHAU1 00000127 09775653

01 FC:1251 110.00 OP

01/28/2003 CCHAU1 00000127 09775653

03 FC:1202 54.00 OP